## Comparative characteristics of electrical and photoelectrical properties of Si/fullerite C<sub>60</sub> and Si/nanocomposite fullerite C<sub>60</sub>:Me (Me=Cu, Al, Sn and Te) heterostructures

Spoiala D.\*, Evtodiev I., Prilepov V.

Moldova State University, MD-2009, Chisinau, Moldova \*e-mail: spodor@usm.md

The electronic structure and optical properties of fullerite  $C_{60}$  thin films are suitable for using in efficient heterojunction solar cells and similar devices. Heterojunction behaviour with high rectifying ratio in the dark ( $k>10^4$  at  $\pm 2$  V) and photovoltage generation were demonstrated, firstly, for a *p*-Si/C<sub>60</sub> interface. Both isotype *n*-Si/C<sub>60</sub>/M and anisotype *p*-Si/C<sub>60</sub>/M heterojunctions (where M=A1, Au, Ti, Nb, etc. are top metallic electrodes) are studied by many scientific groups [1-3]. But very intrinsic conductivity of C<sub>60</sub> thin film ( $\sigma$ ~10<sup>-10</sup>-10<sup>-14</sup>  $\Omega$ ·cm) is considered as one of the main limiting factors for Si/C<sub>60</sub> solar cell efficiency. Therefore, "doping" of fullerite C<sub>60</sub> is one the principal challenges for high efficiency fullerene-based solar cell production [1].

This work presents the results of research on electrical and photo-electrical properties of heterostructures Si/fullerite  $C_{60}$  and Si/nanocomposite fullerite  $C_{60}$ :Me (where Me=Cu, Al, Sn and Te) with various concentrations of Me. For the heterostructures Si/ $C_{60}$  and Si/ $C_{60}$ :Me obtaining, 4 types of silicon plates have been used: *n*-type crystalline Si wafers (111) (doped with P, 0.3 and 4.5  $\Omega$ ·cm) and *p*-type crystalline Si wafers (111) (doped with B, 0.1 and 10  $\Omega$ ·cm). Thin films of fullerite  $C_{60}$  (*d*~0.1–0.5 µm) were obtained by vacuum sublimation of  $C_{60}$  powder. Fullerite  $C_{60}$ :Me thin films (*d*~0.05–0.5 µm) have been prepared by simultaneous deposition of Me and fullerite  $C_{60}$  by double-source coevaporated system. Separately electrical and optical properties of fullerite  $C_{60}$ :Me thin films have been studied. The surface structures of fullerite  $C_{60}$  and fullerite  $C_{60}$ :Me thin films have been studies with atomic force microscope.

Current-voltage characteristics for all obtained heterostructures in darkness and under light illumination are obtained. The analysis of experimental dark current-voltage characteristics is performed being taken into account in the equivalent circuit of heterostructures of series and shunt resistances. At light illumination a photovoltaic effect for all types of obtained heterostructures is observed. The comparative analysis of electrical and photo-electrical properties of Si/fullerite  $C_{60}$  and Si/fullerite  $C_{60}$ :Me heterostructures has been performed.

[3] C.Wen, T.Aida, I.Honma, H.Komiyama, K.Yamada, *Denki Kagaku* 62, 264 (1994).

<sup>[1]</sup> E.A.Katz, Physics of the Solid State 44, 621 (2002).

<sup>[2]</sup> K.M. Chen, Y.Q.Jia, S.X.Jin, K.Wu, X.D.Zhang W.B.Zhao, C.Y.Li, Z.N.Gu, J.Phys.: Cond. Matter. 6, L367 (1994).